

Magnetron Sputter coater

Adeco offers several models of sputter coaters which are well designed with standard features, to meet the academic and research requirements. These models are ideal for the users who demand for high quality thin film deposition, especially conductive coatings, using a user friendly equipment. Magnetron sputtering is a plasma coating process whereby sputtering material is physically removed by bombardment of ions of an inert gas (normally Argon) to the surface of target material. In other words, by applying a high voltage, glow discharge is created, resulting in acceleration of ions. When the argon-ions collide with the target, sputtering materials will be ejected from the target surface, leading to the formation of a coating layer on the products.

Features

- Simple operation
- Compact design
- Glow discharge capability
- DC power supply with a maximum output of 200 mA.
- Pre clean samples before deposition with etching process
- 2 inch sample for excellent conformity and coverage
- 200 V bias voltage
- Adjustable Stage height
- Full color touch screen control provides simple operation.
- Control timed sputter and Etch process set point power, duration and thickness.
- A crystal monitor for online thickness measurement.

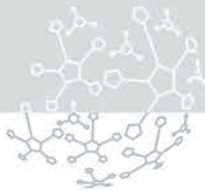
Advantages

- High deposition rate
- Ease of sputtering any metal, alloy or compound
- High-purity films deposition
- Extremely high adhesion of films
- Ability to coat heat-sensitive substrates
- Ease of automation
- Excellent uniformity on large-area substrates

Application

- Microelectronic circuits and chip carriers
- Electrical resistance films, e.g. Ni-Cr for strain gauges
- Magnetic films for general magnetic storage devices, floppy discs, tapes and thin-film magnetic heads.
- Opto-storage devices. e.g. compact discs and video discs.
- Corrosion-resistant films (Cr-Ni)
- Bonding layers
- Coating of noble metals including Gold, Silver and etc.
- Preparation of TEM, SEM samples





SPECIFICATION

Models	Parameters	SUPER SPUTTER COATER	LAB SPUTTER COATER	FAST SPUTTER COATER
Glass Jar Chamber		200×306 cm	200×215 cm	150×120 cm
Turbo Molecular Pump		80 L/s	80 L/s	
Two-Stage Rotary Pump		160 L/m	160 L/m	160 L/m
Rotating Stage		Optional	Optional	
Sputter Gun Position		Bottom	Bottom/Upper	Upper
Thickness Measuring Crystal		✓	✓	
DC Power Supply		200 mA		
RF Power Supply		Optional	Optional	
Co-Sputtering Processes		✓		
2-Inch Diameter Cathode		3	1	1
Mass Flow Control		✓	Optional	
PLC Full-Color Touch Screen		✓	✓	

